

Webinar

Exploring the Grenoble
Semiconductor Ecosystem and
the FAMES Pilot Line

February 2nd, 2026



Bruno Paing, VP Europe & International Public Affairs – CEA-Leti (bruno.paing@cea.fr)



leti

CEA-Leti

Research & Technology
Organization

Grenoble, France



CEA-Leti mission & key figures

Created in **1967**, CEA-Leti is located in **Grenoble**, France

Benefits of a world-leading R&D organization:



A commitment to long-term collaborations

~2,000 experienced research engineers



World-class technological platforms

13,000m² cleanroom space (200 & 300 mm)



Multidisciplinary applied research

3,200 patents in portfolio



Partnerships with industry

300 industrial partners

75+ startups created



Budget: 450M€ (85% from R&D contracts)



At the heart of the French Alps Silicon Valley



nature

How Grenoble has mastered industry-academia science collaborations

Despite its small size, the French city's long history of science and business means it punches above its weight in scientific output.

CEA-Leti semiconductor platforms

300mm & 200mm Si components Platforms

- FD-SOI, Memories, Si Photonic, Power
- 24/7 operations

200mm MEMS Platform

- μ LED, μ display, MEMS
- 24/7 operations

Substrates < 200mm, III-V and II-VI Platform

- μ LED, Sensors
- 1 shift/day

Nano-Characterization Platform

- 8 centers of competences
- 1 shift/day

> 11,000 m² cleanrooms

> 700 equipment

> 650 experts

~ 50 patents

200 publications / year

MEMS 200

Characterization

Photonics

Cleanroom Shuttle

CMOS 200mm & 300mm

cea

leti

700 state-of-the-art tools
11,000 m² cleanroom space

More than Moore

World-class facilities

for your future needs

Main Technology Baselines

Wafer sizes (mm)		
300	1	NW GAA / BEYOND CMOS
200 300	2	EMBEDDED MEMORIES
200 300	3	RF (active and passive devices)
200 300	4	Si PHOTONICS
200 300	5	μLED DISPLAY
300	6	IMAGERS
200	7	MEMS
200 300	8	POWER (Si, GaN, SiC)
200 300	9	3D
200 300	10	SUBSTRATES
200	11	II-VI and III-V

European Chips Act 5 pilot lines



Nano IC: European pilot line for beyond 2nm leading edge system-on-chip leadership



APECS: Advanced Packaging for Electronic Components and Systems and Heterogeneous Integration



FAMES: FD-SOI pilot line for Applications with non-volatile embedded Memories, RF & 3D integration for European Sovereignty



PIXEurope: Advanced Photonic Integrated Circuits Pilot Line for Europe



WBG: Wide Band Gap materials pilot line - GaN & SiC





FAMES Pilot Line Consortium

- Hosting sites
- Skills contributors

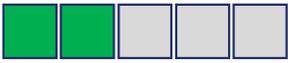
Budget : €830 M

- CAPEX: €382 M
- OPEX: €448 M

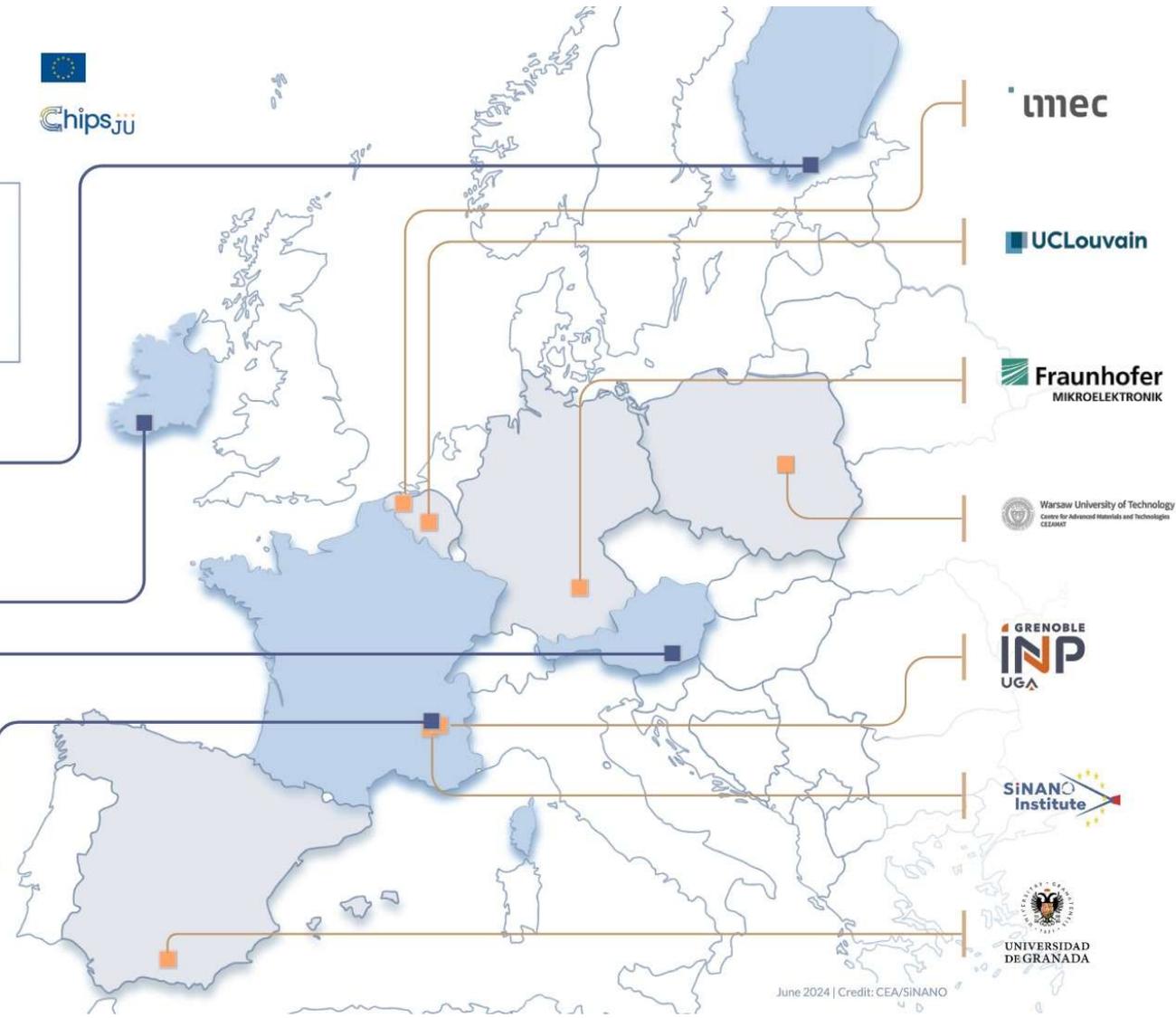
Funding mechanisms

- 50% Chips JU
- 50% Member States

Dec. 2023 → Dec 2028



fames-pilot-line.eu

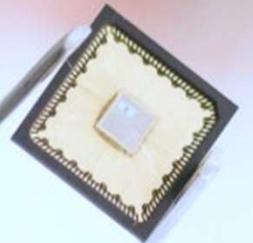


June 2024 | Credit: CEA/SINANO



Aim of FAMES

- A European semiconductor pilot line for advanced technologies
- With opportunities for disruptive chip architectures, performance improvements and significant energy savings
- Strengthening European leadership in advanced semiconductors and opening new economic opportunities for a wide spectrum of markets

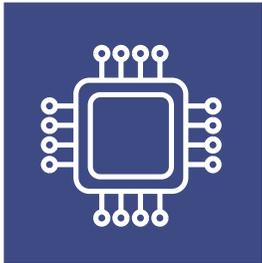


Opening the pilot line to European stakeholders

44 letters of support

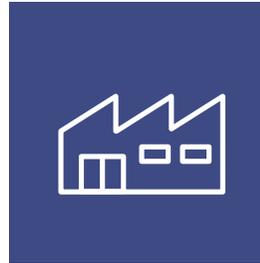


FAMES Key Activities



R&D

**5 Technologies +
an eco-innovation
Program**



**Pilot line
implementation**

**Cleanroom
equipments**



Open-access

**Yearly Calls
Spontaneous
Requests**

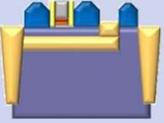
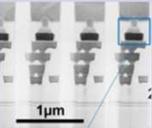
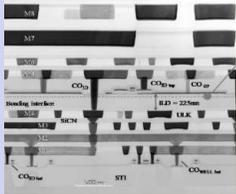
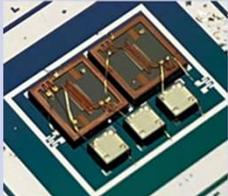


Training & education

**Workshops, webinars
and schools**

FAMES Technology Portfolio

FAMES technological offer

FD-SOI	Embedded non-volatile memories	Radiofrequency components	3D integration	Small inductors for DC-DC converters
<p>10 nm and 7 nm nodes</p>  <p>0,7V 57CPP 48/40MPP</p>	<p>OxRAM, FeRAM, MRAM and FeFET</p>  	<p>Switches, filters, and capacitors</p> 	<p>Heterogeneous and sequential</p> 	<p>Power management integrated circuits (PMIC)</p> 
  	     	  	 	 

Eco-innovation

Evaluate and reduce environmental footprint



Planetary boundaries



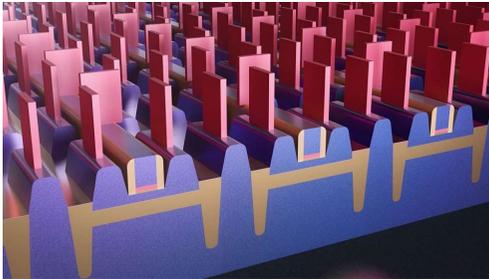
Environmental regulations






FD-SOI is the optimal PPAC-E (Power, Performance, Area, Cost, Environmental impact) trade-off for mixed-signals circuits

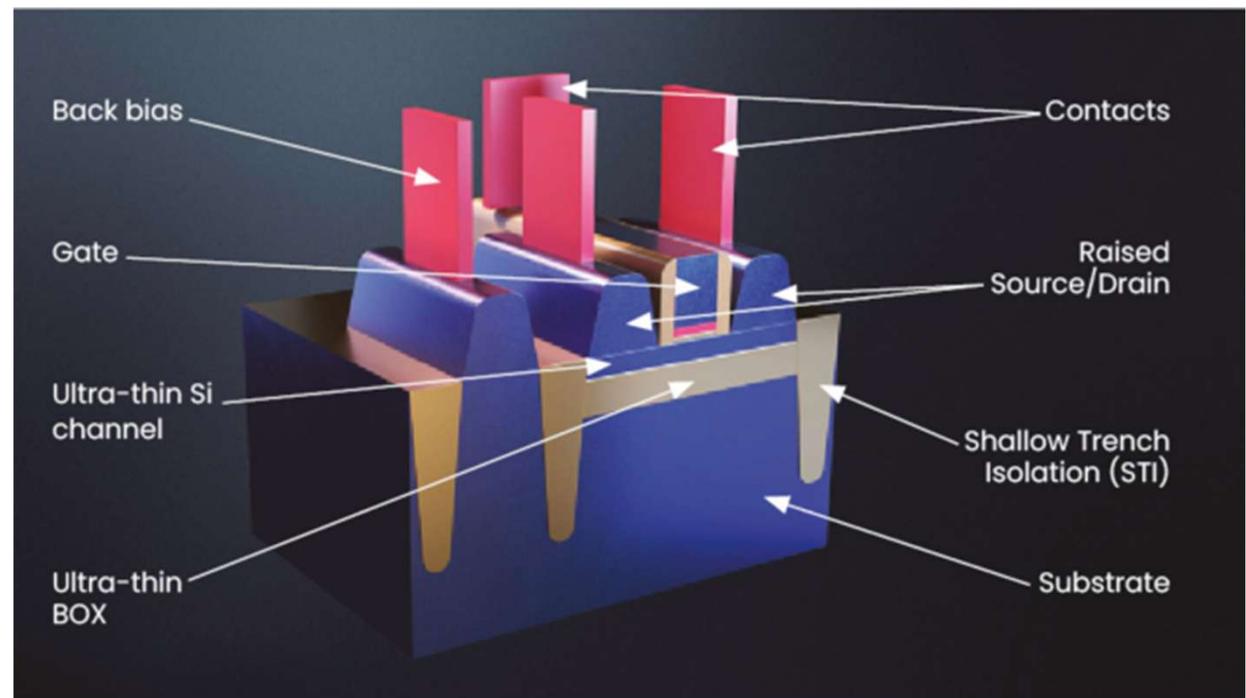
FD-SOI advanced nodes (10 - 7nm)

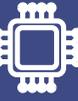


- Transistor density
- High-performance/low-power trade-off
- Radiation resistance
- Reduced current leakage
- Manufacturing costs

- Over **150 patents** filed by CEA-Leti

An innovative generation of chips with the best balance in Power, Performance, Area, Cost and Environment (PPAC-E) for highly energy efficient applications





Radiation resistance, should we matter? Yes, we should...

B B C

Bit flips: How cosmic rays grounded a fleet of aircraft

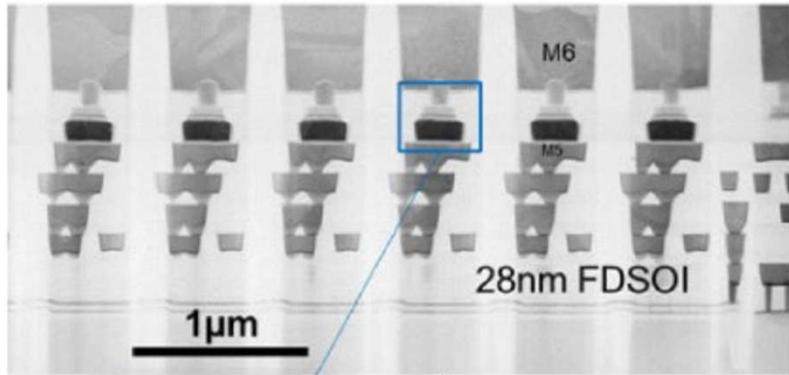


Radiation from space that led to more than 6,000 Airbus aircraft needing emergency computer updates could become a growing problem as ever more microchips run our lives.

More than 100 FD-SOI products on the market in 2025

Wireless communication	Automotive			
<p>5G Smartphones</p> <p><i>mmW Transceiver</i></p> <p>Wi-Fi / Bluetooth LE Modules</p> <p><i>WiFi 7 Multiprotocol MPU Audio MCU with BLE</i></p>	<p>Front-End Camera</p> <p><i>Image Processor</i></p> <p>Thermal Camera</p> <p><i>LWIR Smart Sensor</i></p> <p>Radar</p> <p><i>77-120 GHz SoC</i></p> <p>Digital Cockpit</p> <p><i>Multi-media MCU</i></p> <p>E-Powertrain</p> <p><i>32 bits MCU</i></p>			
	Wearables		Embedded Computing	Aerospace
	<p>Smartwatches</p> <p><i>Crossover MCU GNSS</i></p> <p>Smartglasses</p> <p><i>Audio Processor Display Driver</i></p> <p>Earphones</p> <p><i>Audio Processor</i></p>		<p>Edge AI</p> <p><i>NPU FPGA USB Stick</i></p> <p>Cameras</p> <p><i>Image Processors</i></p> <p>Smart Speakers</p> <p><i>Audio Processor</i></p>	<p>Satellites</p> <p><i>Transceiver</i></p> <p><i>FPGA</i></p> <p>Avionics</p> <p><i>MCU</i></p>
			Quantum Computing	
			<p><i>quobly QPU equal1</i></p>	

Emerging Non-Volatile Memories embedded in the BEOL



L. Grenouillet et al. IMW'21
G. Molas et al., IMW'22

EMBEDDED

quicker access time and lower power compared to stand alone as they are on chip close to the logic

NON VOLATILE

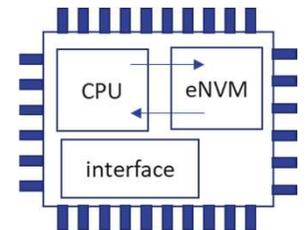
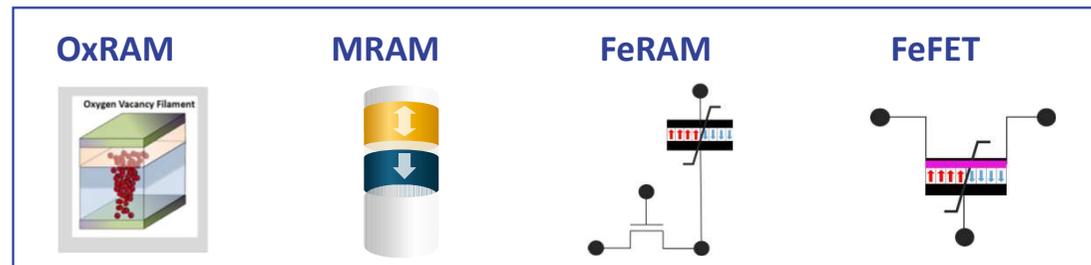
retaining data even when the power is off

PERFORMANT

reprogrammable and erasable multiple times, faster to write compared to Flash memories

LOW POWER

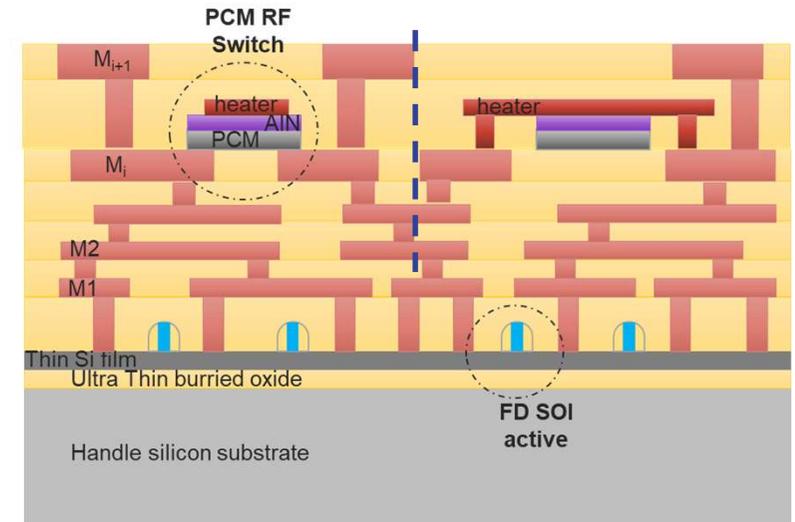
lower power consumption than external non volatile memories



RF components integrated in the BEOL

FD-SOI is well-suited for RF/analog and mixed signal circuits

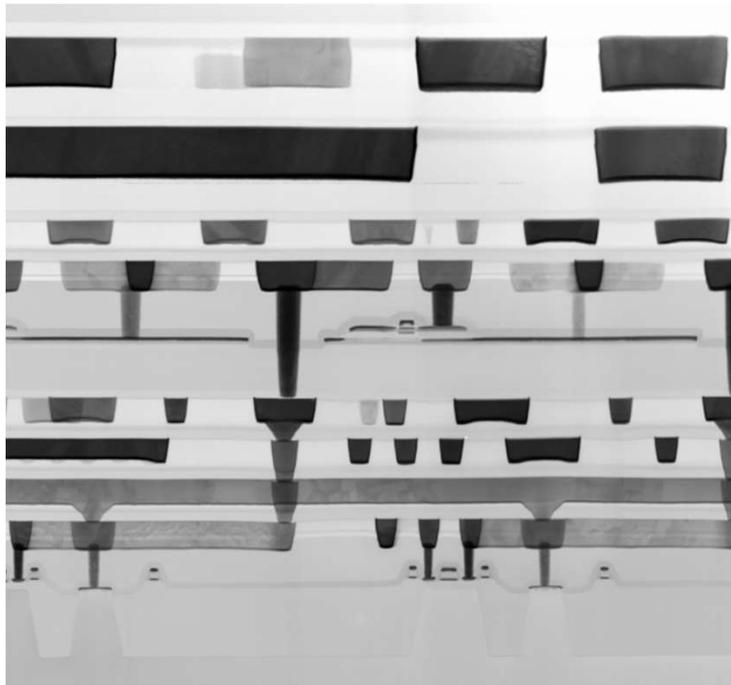
- Performance/power savings
- Covering a wide frequency range
- From a few GHz up to the D-band centered at 140 GHz



FAMES → RF active and **passive components**, to enrich the FD-SOI CMOS technology offer and open new markets:

- RF switches based on Phase Change Materials
- RF acoustic filters
- RF magnetic-based miniaturized circulators for >GHz bands

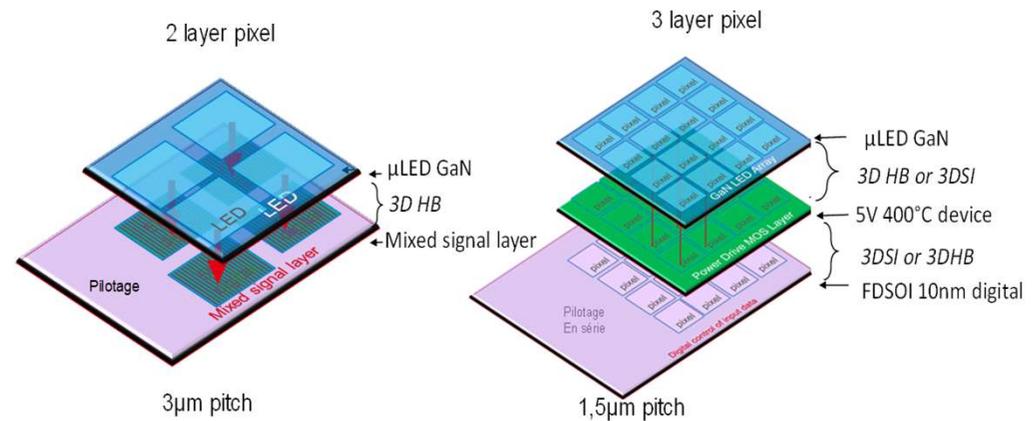
3D Sequential integration



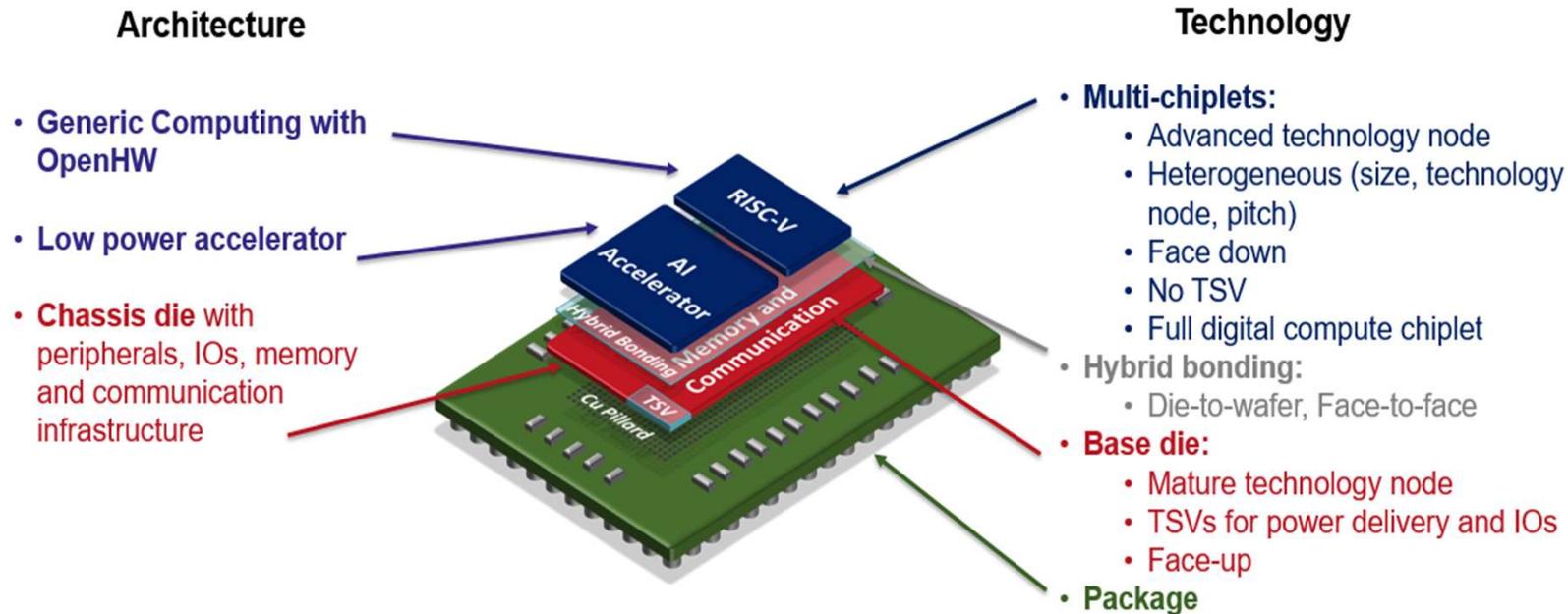
FAMES aims to enlarge FD-SOI heterogeneous co-integration with other devices using 3DSI to address new systems and markets

- Demonstrate 3D sequential integration with increasingly complex circuits;
- Evaluate opportunity of Smart and scaled 3tier-pixels with GaN μ LED and RF applications

“High Performance 2.5 V n&p 400 °C SOI MOSFETs: A Breakthrough for Versatile 3D Sequential Integration,” D Bosch et al. IEDM 2025



Edge computing based on 3D hybrid bonding (HB) chiplet architecture

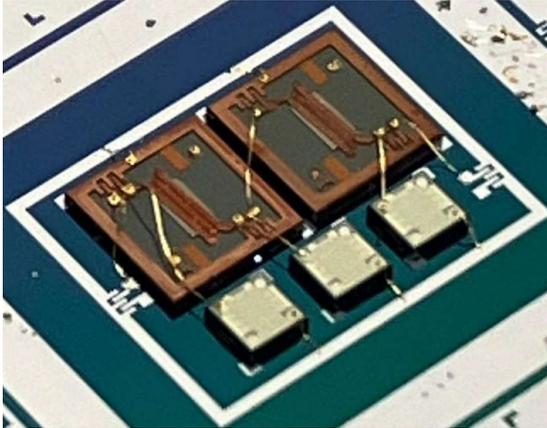


Novel 3D approach developed by FAMES: Chiplet architecture with very low latency

- TSV : Back-Side Mid-BEOL TSVs
- Cu/SiO2 HB : 5 μ m pitch
- Front-Side and Back-Side RDLs

➔ To increase interconnect density by a factor of up to 100

Integrated Magnetics and PMIC for DC-DC power conversion



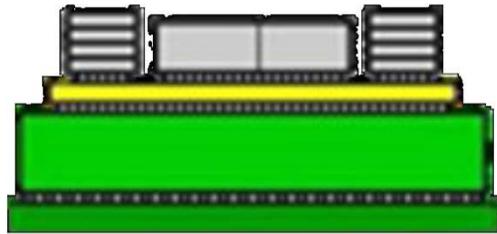
Power management integration in Systems-on-Chip

- Power converters densely co-integrated with digital or RF loading blocks
- Solutions to improve **power delivery** in chiplet architectures
- **Integration of passive components close to SOC**
- Design and fabrication of **integrated magnetics for inductive passive components**

FAMES will provide solutions to improve power delivery by integrating passive components into SOC

- Design and fabrication of integrated magnetics for inductive passive components
- Collective assembly of passives by Micro Transfer Printing (MTP)
- Performance assessments via a functional technology demonstrator that integrates an inductance-based DC-DC power converter, for granular power delivery

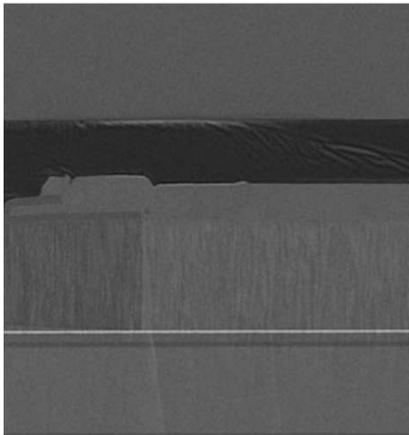
Power conversion: 3D caps



Hybrid integration

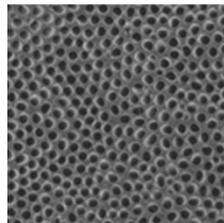
Hybrid integration of high density capacitors and CMOS power conversion stages on 300mm wafers for advanced 6G systems and HPC applications

- Very high density capacitors:
 - Specific ALD method developed for a MIM deposition with aggressive aspect ratios
 - TiN bottom and top electrodes
 - Si oxide and/or alumina for dielectrics



T = 5.00 kV
Grand. = 1.53 K X
Signal A = SE2
Mixage Signal = 0.0000

Higher surface capacitors



High A/R MIM

A game-changer for power signal management

FAMES Eco Innovation Offer

Eco-innovation for more sustainable electronics
Reducing the impacts of electronics through R&D

- The development and implementation of **lifecycle analysis (LCA)**
- The validation of eco-innovative solutions in a production-like environment
- The development of technologies and end-to-end systems to meet specific environmental criteria for identified use cases.

16 environmental footprint criteria



New facility and Pilot Line tool capability in Europe



January 30, 2026

Credit: P Jayet / CEA

**New cleanroom at CEA-Leti
2000m² double basement state of the art facility**

**Procurement of 100+ pieces of equipment
planned by the Pilot Line on 4 hosting sites**

- France 
- Finland 
- Ireland 
- Austria 

FAMES year 1 results highlights

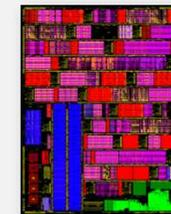
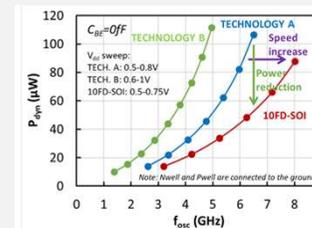
Infrastructure and procurement

- New cleanroom at CEA-Leti planned for delivery in 2025
- 24 pieces of equipment installed /15 ready for production
- **Official inauguration on October 17th, 2025**

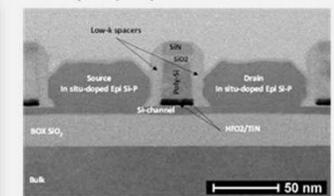


FD-SOI

- FD-SOI 10nm process assumptions ready for perf. evaluation
- First FD-SOI 10nm DRM and first GDS ready for tapeout
- Key process modules and FD-SOI10 architecture developed on relaxed pitch



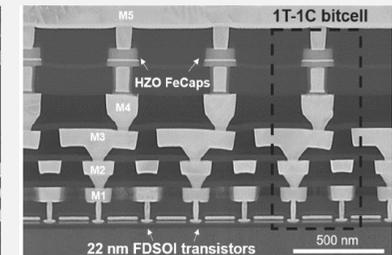
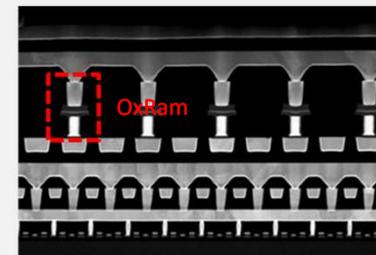
NMOS after epitaxy



C28nm design rules

eNVM

- OxRAM 0.05 μm bit-cell tested
- FeRAM test vehicle characterized: **best state of the art** presented at IEDM2024
- Wafer scale MoS2 growth demonstrated



Accessing the FAMES Pilot Line

The FAMES Pilot Line is open to all types of Users



LARGE COMPANIES



SMEs



START-UPS



RESEARCH COMMUNITY



Design Houses
Fabless
Foundries
Integrated Device Manufacturers
Material and Tool Suppliers
Universities
Research Centers

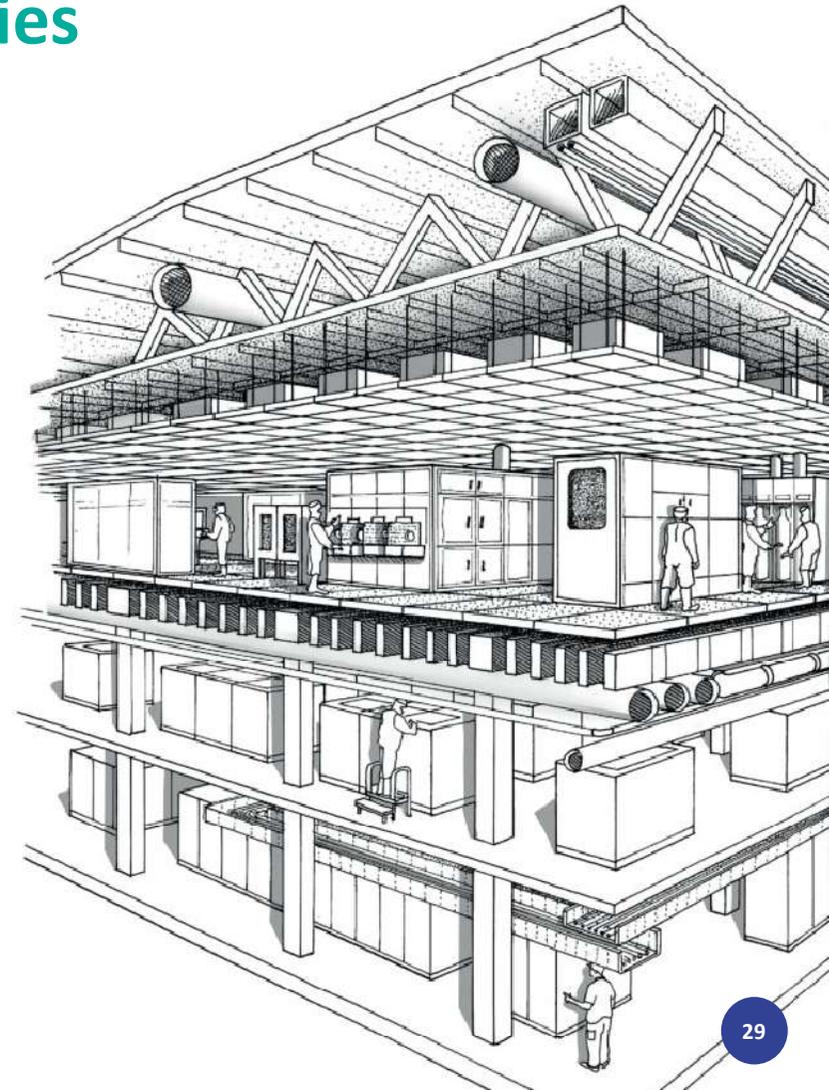
FAMES European open-access Pilot Line for advanced semiconductor technologies

Aim: Facilitate the adoption of FAMES Technologies to strengthen the European semiconductor ecosystem

To gain access to:

- Two types of PDKs (multi-project wafer or IC design assessment)
- The FAMES technologies (FD-SOI advanced nodes, embedded non-volatile memories, RF components, 3D integration options, PMIC) for performance evaluation
- Specific process steps, modules, integration flows, and demonstrator results
- Education and training on the FAMES technologies

as they become available



The FAMES Pilot Line's synergy with the Research Community



RESEARCH COMMUNITY

- Leverage PDKs to create innovative IPs leading to new fabless start-ups
- Collaborate with FAMES partners and provide feedback on first PDK releases
- Define disruptive chip architectures for new ICs
- Get young researchers trained on FD-SOI and FAMES technologies to increase the emergence of EU-made breakthrough chips

Two ways for Users to access the FAMES Pilot Line



Yearly Open-Access Calls
March to May

 fames-pilot-line.eu

Spontaneous Requests
All year round

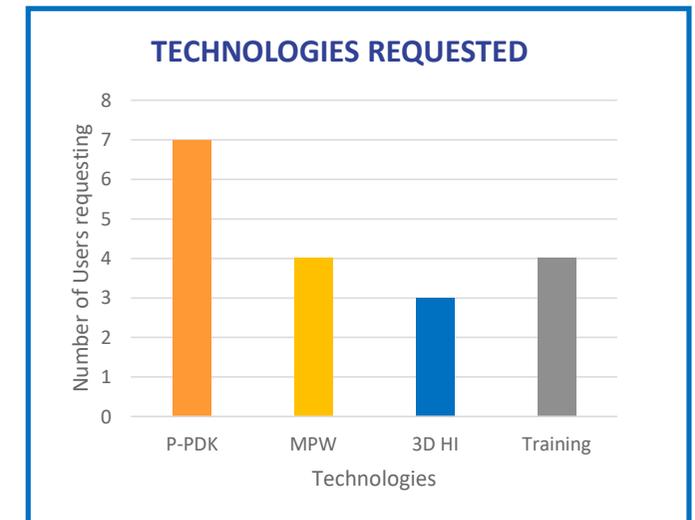
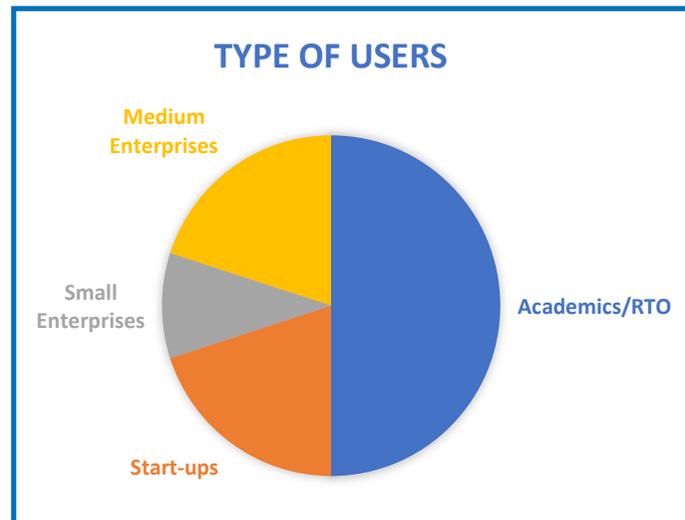
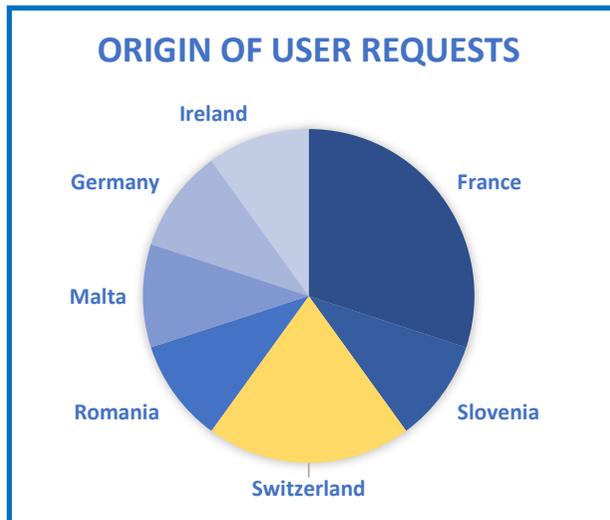
 fames-pilot-line.eu



Competence centers and Design Platforms

User Requests received / first FAMES Open-Access Call (2025)

- **Domains:** Telecommunications, Quantum, Cognitive and Edge AI, Power Management, Chip Design Tools, Teaching



 **FAMES**

greener electronics

FD-SOI • NVM • 3D • RF • PMIC

FAMES 2026

Open-Access Call Launch

The FAMES Pilot Line



fames-pilot-line.eu

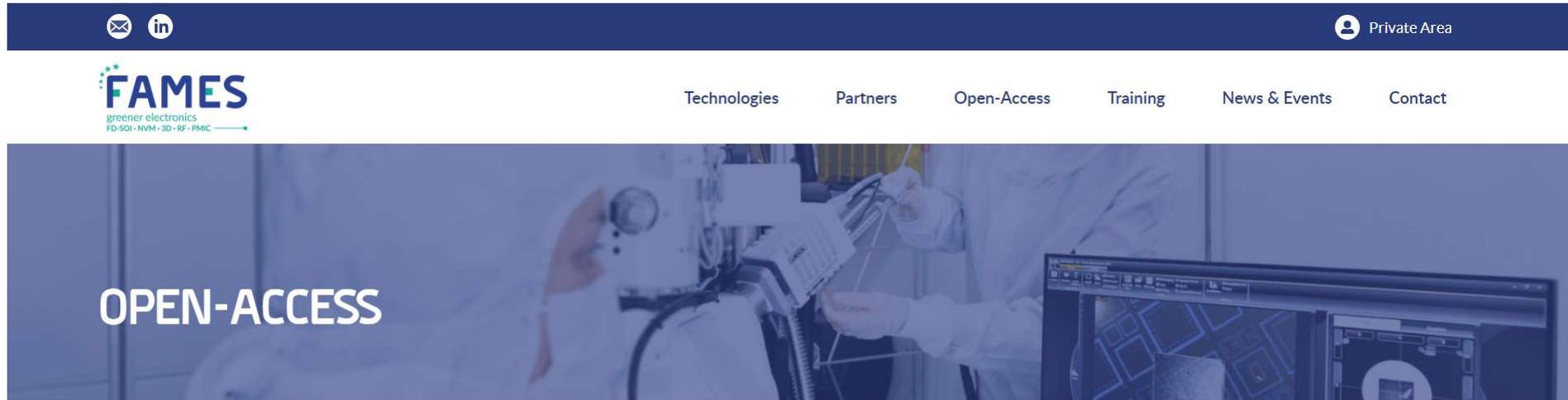
 When

March 9, 2026

 Where

Full Remote Event

Website: Open-Access page



FAMES Pilot Line

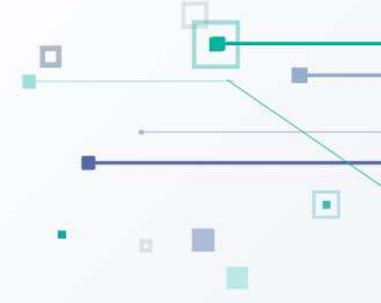
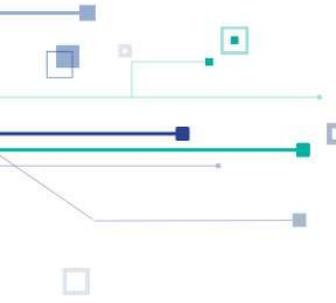
The FAMES Pilot Line offers European semiconductor stakeholders from industry, research, and academia **access to a unique slate of advanced semiconductor technologies**, chip design, testing, demonstrators and manufacturing capabilities.

This initiative aligns with the EU Chips Act to bolster the EU's semiconductor industry and support European technological sovereignty. Collaboration with other pilot lines in Europe will help build a tightly interconnected European chip ecosystem.

Follow the FAMES Pilot Line on LinkedIn! 



@fames-pilot-line

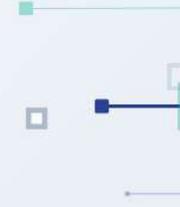


FAMES

greener electronics
FD-SOI • NVM • 3D • RF • PMIC



(2023 – 2028)



Sponsors

The FAMES Pilot Line of the Chips JU is funded by Horizon Europe and Digital Europe Programs and the National Public Authorities of the partners involved. Grants N° 101182279 and 101182297.



R.E.S.O.L.V.E

ENERGY
EFFICIENCY
GAIN
× 1,000
by 2032

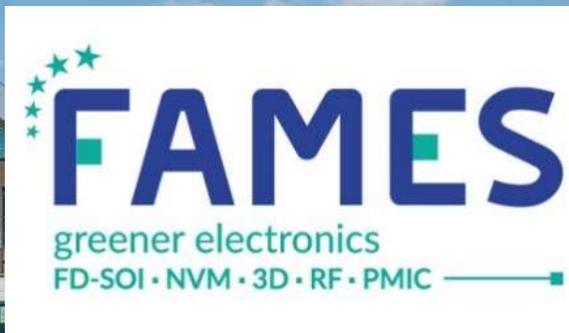
RESOLVE Initiative

Towards Chips Act 2

Reducing
Energy consumption for
SOvereignty and
Leadership in
Value-added
Electronics products



Contact: bruno.paing@cea.fr



PARTNER WITH US
to fast track
your innovation project